Call for Papers – DPS 2026

47th International Symposium on Dry Process

November 19(Thu) - 20(Fri), 2026

Tokyo International Exchange Center, Plaza Heisei, Tokyo, Japan

Paper Submission Deadline: July 21, 2026
Author instructions and information about DPS can be found at:
https://www.dry-process.org/2026/

The 47th International Symposium on Dry Process (DPS2026) will be held at Tokyo International Exchange Center, Plaza Heisei, Tokyo, Japan from November 19 to 20, 2026. The Symposium covers all aspects of the rapidly evolving fields of dry processes, including but not limited to plasma etching and deposition processes, diagnostics and modeling of plasmas and surfaces, and surface modifications by plasmas, for the applications in, e.g., microelectronics, power devices, sensors, environmental protection, biological systems, and medicine. The DPS has provided valuable forums for in-depth discussion among professionals and students working in this exciting field for more than four decades.

Theme: Dry processes and related technologies from fundamentals to applications

Topics:

1. Etching Technologies
2. Manufacturing Technologies (AEC, APC, EES, FDC)
3. Surface Reaction and Damage
4. Plasma Diagnostics and Monitoring Systems
5. Computational Approaches (Modeling, Simulation, Machine Learning, AI, Informatics, DX) for Dry Process
6. Plasma Generation (Equipment/Source)
7. Deposition Technologies (CVD / PVD)
8. Atomic Layer Processes (ALD/ALE)
9. Dry process for Green Transformation: GX (Energy saving technology, Alternative gas, Sustainability)
10. Plasma Processes for New Material Devices (MRAM, Power, Organic, III-V, 2D)
11. Plasma Processes for Biological and Medical application, MEMS
12. Atmospheric Pressure Plasma and Liquid Plasma
13. New Dry Process Concepts
14. Dry Processes for 3D-IC / Packaging

Arranged session :

AS1-Challenges and breakthroughs in high-aspect-ratio processes: etching and deposition
AS2-Modeling, simulation, and digital twins for future dry process development
AS3-Ultimate control of surface reactions at the atomic scale

For further general information, please contact: e-mail: dps2026@officepolaris.co.jp

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URL: https://www.dry-process.org/2026/